

Notice of References Cited	Application/Control No. 10/725,063		Applicant(s)/Patent Under Reexamination OHMI ET AL.	
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U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-6,350,322 B1	02-2002	Yates, Donald L.	134/3
*	C	US-6,066,571 A	05-2000	Usuda et al.	438/745
*	D	US-5,439,569 A	08-1995	Carpio, Ronald A.	134/1.3
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Author unknown, IBM Technical Disclosure Bulletin #NN9201295 entitled "Deoxygenated HF Acid Solutions for Precleaning of Silicon Wafer", dated January 1, 1992, 2 pages.
	V	Bok et al., "Alternative NH ₄ F/HCL solution for ultraclean Si(001) surface", J. Vac. Sci. Technol. A 18(5), October 2000, pages 2542-2548.
	W	Endo et al., "Atomic structures of hydrogen-terminated Si(001) surfaces after wet cleaning by scanning tunneling microscopy", Applied Physics Letters, September 1998, Vol. 73, No. 13, pages 1853-1855.
	X	Shwartzman et al., "Megasonic Particle Removal from Solid-state wafers", RCA Review, Vol. 46, March 1985, pages 81-105.

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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	U	Kern, "Overview and Evolution of Semiconductor Wafer Contamination and Cleaning Technology", pages 1-66.
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